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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/790,828	03/03/2004	Masakiyo Matsumura	249687US2	1522
22850 7590 01/02/2008 OBLON, SPIVAK, MCCLELLAND MAIER & NEUSTADT; P.C.			EXAMINER	
1940 DUKE	940 DUKE STREET		SONG, MATTHEW J	
ALEXANDR	IA, VA 22314		ART UNIT PAPER NUMBER	
			1792	
			NOTIFICATION DATE	DELIVERY MODE
			01/02/2008	ELECTRONIC

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

Notice of the Office communication was sent electronically on above-indicated "Notification Date" to the following e-mail address(es):

patentdocket@oblon.com oblonpat@oblon.com jgardner@oblon.com

Office Action Summary		Application No.	Applicant(s)		
		10/790,828	MATSUMURA ET AL.		
		Examiner	Art Unit		
		Matthew J. Song	1792		
Period fo	The MAILING DATE of this communication app or Reply	ears on the cover sheet with the	correspondence address		
A SH WHIC - Exte after - If NC - Failu Any	ORTENED STATUTORY PERIOD FOR REPLY CHEVER IS LONGER, FROM THE MAILING DANSIONS of time may be available under the provisions of 37 CFR 1.13 SIX (6) MONTHS from the mailing date of this communication. Depriod for reply is specified above, the maximum statutory period ware to reply within the set or extended period for reply will, by statute, reply received by the Office later than three months after the mailing ed patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION B6(a). In no event, however, may a reply be the trill apply and will expire SIX (6) MONTHS from cause the application to become ABANDON	DN. timely filed m the mailing date of this communication. IED (35 U.S.C. § 133).		
Status					
1)⊠	Responsive to communication(s) filed on <u>05 Oc</u>	<u>ctober 2007</u> .			
2a)□	This action is FINAL . 2b)⊠ This	action is non-final.			
3)□	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is				
	closed in accordance with the practice under E	x parte Quayle, 1935 C.D. 11, 4	153 O.G. 213.		
Dispositi	ion of Claims				
5)□ 6)⊠ 7)□	Claim(s) 3,5,11,15-18 and 20-39 is/are pending 4a) Of the above claim(s) 20-38 is/are withdraw Claim(s) is/are allowed. Claim(s) 3, 5, 11, 15-18, and 39 is/are rejected. Claim(s) is/are objected to. Claim(s) are subject to restriction and/or	n from consideration.			
Applicati	on Papers				
10)	The specification is objected to by the Examiner The drawing(s) filed on is/are: a) access Applicant may not request that any objection to the conference of Replacement drawing sheet(s) including the correction of the oath or declaration is objected to by the Examiner.	epted or b) objected to by the drawing(s) be held in abeyance. Se on is required if the drawing(s) is ol	ee 37 CFR 1.85(a). bjected to. See 37 CFR 1.121(d).		
Priority u	ınder 35 U.S.C. § 119				
12) a)[Acknowledgment is made of a claim for foreign All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the priori application from the International Bureau see the attached detailed Office action for a list of	have been received. have been received in Applicative documents have been received (PCT Rule 17.2(a)).	tion No red in this National Stage		
Attachment	• •	A) 🔲 laton dow Sum	v (PTO 413)		
2) Notice 3) Inform	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948) nation Disclosure Statement(s) (PTO/SB/08) r No(s)/Mail Date	4) Interview Summary Paper No(s)/Mail D 5) Notice of Informal I 6) Other:	Date		

DETAILED ACTION

Continued Examination Under 37 CFR 1.114

1. A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on 10/5/2007 has been entered.

Claim Rejections - 35 USC § 102

2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 3. Claims 3, 5, 11 and 39 are rejected under 35 U.S.C. 102(b) as anticipated by Taniguchi (US 5,710,620).

Taniguchi discloses an apparatus comprising a phase shifted reticle where the angle of diffracted light generated from a pattern of the reticle varies with the line width and pitch of the pattern (col 10, ln 15-40 and col 12, ln 45-60), this reads on applicant's phase modulation element. Taniguchi also teaches an illumination system 1 used to generate light beams which enter the phase modulation element (col 5, ln 1-15 and col

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10, ln 15-30). Taniguchi also teaches an image formation optical system **7A**, **8** provided on an outgoing radiation side of the phase modulation element **R** (col 5, ln 1-67 and Fig 1). Taniguchi also discloses a stage **WS** for holding a wafer **W** (col 6, ln 45-65 and Fig 1). Taniguchi also teaches the phase shift reticle (phase modulation element) has at least two phase modulation elements and is configured to transmit light (Fig 3A). Taniguchi also teaches a plane which is orthogonal to a light incidence direction being defined by a first and second direction (Fig 1 shows the light vertical and the reticle horizontal and the reticle extends in the vertical and horizontal directions in Fig 11A). Taniguchi also teaches strip like areas which extend parallel to the second direction and to which first and second phase values are given. (Fig 11A and 12A show strip like areas and discloses a plurality of normal patterns with different preciseness (line width and pitch) (col 12, ln 40-65), thus produces different phase values).

Regarding the limitation, "each of the phase modulation units is optically smaller than a radius of a point spread distribution range of the image formation optical system when converted to an image formation surface to the image formation optical system and the radius of the point spread distribution range of the image formation optical system is defined to satisfy the follow equation:" and "the phase modulation element has a plurality of cells each of which is optically smaller than the radius of the point spread distribution range of the image formation optical system converted to the image formation surface"

The limitation is an intended use limitation based on the desired radius of a point spread distribution from the optical system. A recitation of the intended use of the claimed invention must result in a structural difference between the claimed invention and the prior art in order to patentably distinguish the claimed invention from the prior art. If the

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prior art structure is capable of performing the intended use, then it meets the claim. Taniguchi discloses all of the apparatus limitation, as discussed previously, and the apparatus is capable of changing the illumination conditions, ring zone illumination and grading illumination by the arrangement of the parts, thus would be capable of the producing a point spread distribution radius which is optically large than the phase modulation element. The same argument applies to claims 3, 5, 11 and 39 directed to features of the phase modulation element compared to the radius of a point spread distribution.

Referring to claim 39, claim 39 has all of the same limitations as claim 3, which was discussed previously. Claim 39 further requires "in at least one direction" which is met because the apparatus is capable of producing a radius of a point spread distraction range of the image formation optical system that is larger than the phase modulation element is at least one direction.

Claim Rejections - 35 USC § 103

- 4. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were

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made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).

5. Claims 15-18 are rejected under 35 U.S.C. 103(a) as being unpatentable over Taniguchi (US 5,710,620) as applied to claims 1-14 and 19 above, and further in view of Applicant's admitted prior art (AAPA)

Taniguchi discloses all of the limitations of claim 15, as discussed previously, except the phase modulation element turns the incident light beam to a light intensity distribution with a concave pattern that a light intensity in increased toward the periphery from a central area having a first intensity.

In a method of manufacturing a semiconductor, AAPA teaches a phase shifter and light absorption distribution are combined to irradiate a film with light beams having a intensity including a concave pattern and an inverse pattern (pg 3, line 1 to pg 4, ln 25 of the specification). It would have been obvious to a person of ordinary skill in the art at the time of the invention to modify Taniguchi by using the phase shifter taught by AAPA to produce a desirable light intensity pattern for the manufacture of semiconductors.

Referring to claim 16-18, the combination of Taniguchi and AAPA teaches concave and an inverse peak pattern.

Response to Arguments

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6. Applicant's arguments filed 10/5/2007 have been fully considered but they are not persuasive.

Applicant alleges that the apparatus is not taught by Taniguchi is noted but not found persuasive. Taniguchi teaches all of the limitations, as discussed previously; therefore the argument is not persuasive.

Conclusion

7. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

Shiraishi (US 5,715,089) teaches a pattern of stripe and pixels (Fig 7A and 7C).

Kunii et al (US 6,388,386) teaches modulating a intensity of light beam using a cyclic light and dark pattern using a line, wavy lines and grid pattern (Abstract and Fig2A-2D).

Lin et al (US 5,539,568) teaches the size of the beam of light modulated by each pixel or element of the phase modulator should be no larger than the minimum feature of the mask (col 7, ln 40-65).

8. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Matthew J. Song whose telephone number is 571-272-1468. The examiner can normally be reached on M-F 9:00-5:00.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Michael Barr can be reached on 571-272-1414. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Matthew J Song Examiner

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MJS

December 20, 2007

PRIMARY EXAMINED